Title (en)

DEVICE FOR CLEANING METAL SURFACES AFTER THEY HAVE BEEN WORKED AT HIGH TEMPERATURES

Title (de)

VORRICHTUNG ZUR REINIGUNG VON METALLEN NACH DEREN BEARBEITUNG MIT HOHEN TEMPERATUREN

Title (fr)

DISPOSITIF SERVANT AU NETTOYAGE DE METAUX APRES LEUR TRAITEMENT A HAUTE TEMPERATURE

Publication

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Application

EP 96930346 A 19960827

Priority

- IT 9600165 W 19960827
- IT MO950131 A 19950927
- IT MO950156 A 19951110

Abstract (en)

[origin: WO9712081A1] The device proposed for cleaning metal surfaces consists of a pad (12, 34, 91) of insulating material held between a beak-shaped (11, 52, 94) electrode (10, 26, 46) and the metal surface (8) to be cleaned, plus a low-voltage a.c. power supply (2) which is connected via the other electrode to the metal (7). A pump supplies the pad with a highly corrosive, high-density, acid solution. The pad consists of relatively thick hose or tape. The device has slots (36) into which the gases and vapours produced during cleaning are drawn by an extractor fan (40) and then passed through a washing bottle (41) where they are cleaned. The electrode may have various shapes, and it is possible to replace the tip (28, 94, 98). The electrode is preferably designed with bores through which the acid solution can be fed. The main body (97) of the electrode and the replaceable tip (94, 98) may be coated with a layer (101, 100) of insulating material which prevents short-circuits occurring and concentrates the electrolytic action at the end surface (102) of the electrode. Woven or felt fabric made of polyetheretherketone is preferably used as the insulating material of the pad. The lifetime and working capacity of the device are maximized by using a double-layer pad (92, 93), the inner layer being made of woven fabric (92) and the outer layer of felt (93).

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IPC 8 full level

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IPC 8 main group level

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